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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/540,515	06/23/2005	Tsuyoshi Nakano	Q88663	6621
23373 7:	590 01/24/2006		EXAMINER	
SUGHRUE MION, PLLC			HARRISON, MONICA D	
2100 PENNSYLVANIA AVENUE, N.W. SUITE 800			ART UNIT	PAPER NUMBER
	N, DC 20037	·	2813	
			DATE MAILED: 01/24/2006	

Please find below and/or attached an Office communication concerning this application or proceeding.

		Application No.	Applicant(s)	<u></u>
		10/540,515	NAKANO ET AL.	
	Office Action Summary	Examinér	Art Unit	
		Monica D. Harrison	2813	
eriod fo	The MAILING DATE of this communication app r Reply	ears on the cover sheet wit	th the correspondence addre	ess
WHIC - Exten after: - If NO - Failur Any r	CORTENED STATUTORY PERIOD FOR REPLY THEVER IS LONGER, FROM THE MAILING DAISIONS of time may be available under the provisions of 37 CFR 1.13 SIX (6) MONTHS from the mailing date of this communication. period for reply is specified above, the maximum statutory period we to reply within the set or extended period for reply will, by statute, eply received by the Office later than three months after the mailing and patent term adjustment. See 37 CFR 1.704(b).	ATE OF THIS COMMUNIC 36(a). In no event, however, may a re vill apply and will expire SIX (6) MONT cause the application to become AB/	CATION. sply be timely filed IFHS from the mailing date of this command ANDONED (35 U.S.C. § 133).	
tatus				
1)🛛	Responsive to communication(s) filed on 23 Ju	<u>ıne 2005</u> .		
2a)□	This action is FINAL . 2b)⊠ This	action is non-final.		
3) 🗌	Since this application is in condition for allowar			nerits is
	closed in accordance with the practice under E	x parte Quayle, 1935 C.D.	. 11, 453 O.G. 213.	
Dispositi	on of Claims			
4) 🖾	Claim(s) 1-8 is/are pending in the application.			
	4a) Of the above claim(s) is/are withdraw	wn from consideration.		
•	Claim(s) is/are allowed.			
•	Claim(s) <u>1-8</u> is/are rejected.			
-	Claim(s) is/are objected to.	- ala atian maguiramant		
8)[_]	Claim(s) are subject to restriction and/o	r election requirement.		
Applicati	on Papers			
	The specification is objected to by the Examine			
10)⊠	The drawing(s) filed on 23 June 2005 is/are: a)			
	Applicant may not request that any objection to the			1 101/4)
44)[7	Replacement drawing sheet(s) including the correct The oath or declaration is objected to by the Ex			
11)	The path or declaration is objected to by the Ex	tammer. Note the attached	Office Action of form FTO	-152.
Priority (ınder 35 U.S.C. § 119			
	Acknowledgment is made of a claim for foreign	priority under 35 U.S.C. §	119(a)-(d) or (f).	
a)	All b) Some * c) None of: A	s have been received		
	1. Certified copies of the priority document2. Certified copies of the priority document		nnlication No	
	3. Copies of the certified copies of the prior			age
	application from the International Bureau			•
* 5	See the attached detailed Office action for a list		received.	
		·		
• • •				
Attachmen	u(s)			

1) Notice of References Cited (PTO-892)

2) Notice of Draftsperson's Patent Drawing Review (PTO-948)

3) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08)
Paper No(s)/Mail Date かたい イロック

9/20/05

4) Interview Summary (PTO-413) Paper No(s)/Mail Date. _____.

6) Other: __

5) Notice of Informal Patent Application (PTO-152)

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DETAILED ACTION

Priority

1. Receipt is acknowledged of papers submitted under 35 U.S.C. 119(a)-(d), which papers have been placed of record in the file.

Claim Rejections - 35 USC § 102

The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

(b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.

Claims 1-8 are rejected under 35 U.S.C. 102(b) as being anticipated by Johnson et al (6,429,103 B1).

- Regarding claim 1, Johnson et al discloses a semiconductor epitaxial substrate for use a pseudomorphic high electron mobility field effect transistor, comprising an InGaAs layer as a channel layer (Figure 3, reference 20) and an InGaP layer containing n-type impurities as a front side electron supplying layer (Figure 3, reference 11; column 2, lines 52-56), said InGaAs layer having an electron mobility at room temperature (300 K) of 8000 cm²/Vs or more (Figure 2).
- 3. Regarding claim 2, Johnson et al discloses an InGaP layer as a front side spacer layer between said channel layer and said front side electron supplying layer (Figure 3, reference 11).
- 4. Regarding claim 3, Johnson et al discloses an InGaP layer containing n-type impurities also as a back side electron supplying layer and comprising an InGaP layer as a back

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side spacer layer between said channel layer and said back side electron supplying layer (Figure 3).

- 5. Regarding claim 4, Johnson et al discloses wherein an In composition of the InGaAs layer constituting of said channel layer is 0.25 or more (Figure 3, reference 20).
- 6. Regarding claim 5, Johnson et al discloses wherein GaAs layers each of which has a thickness of 4 nm or more are laminated on said channel layer in contact with a top surface and a bottom surface of said channel layer, respectively (column 2, lines 42-51).
- 7. Regarding claim 6, Johnson et al discloses that an epitaxial layer of each compound semiconductor is formed by employing an MOCVD method (column 1, lines 54-67 thru column 2, lines 1-9).
- 8. Regarding claim 7, Johnson et al discloses that an epitaxial layer of each compound semiconductor is formed by employing an MOCVD method (column 1, lines 54-67 thru column 2, lines 1-9).
- 9. Regarding claim 8, Johnson et al discloses that an epitaxial layer of each compound semiconductor is formed by employing an MOCVD method (column 1, lines 54-67 thru column 2, lines 1-9).

Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Monica D. Harrison whose telephone number is 571-272-1959. The examiner can normally be reached on M-F 7:00am-3:30pm.

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If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Carl Whitehead Jr. can be reached on 571-272-1702. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Monica D. Harrison AU 2813

mdh January 20, 2006

LAURA M. SCHILLINGER PRIMARY EXAMINER